
[Image for reference only. Not to scale.]

Description MgO doped PPLN SHG crystal for around 1080nm<br>Thickness(z) $0.5 \mathrm{~mm} \pm 0.05 \mathrm{~mm}$<br>Width(y) $10 \mathrm{~mm} \pm 0.5 \mathrm{~mm}$<br>Length( x ) $20 \mathrm{~mm} \pm 0.5 \mathrm{~mm}, 1 \mathrm{~mm} \pm 0.1 \mathrm{~mm}$<br>Periods( $\wedge$ ) 6.90, 7.10, 7.30, 7.50, $7.70 \mu \mathrm{~m}$

## NOTES:

1 The SHG device material is Magnesium doped Lithium Niobate with five periodically poled gratings. Each grating is 0.5 mm wide with individual periods as listed above. A saw-cut reference mark is provided on the $+z$ face of the crystal to determine the largest grating period (see above diagram). Each poled grating is separated by 0.2 mm wide regions of unpoled material.

2 The average mark-to-space ratio of each grating is better than 70:30.
3 Each device is etched to make the poled gratings visible. Due to the wet-etch nature of this process the top and bottom surface finish of each device may appear cloudy or uneven.

4 Perpendicularity of input/output facets F1 and F2 to gratings is within $\pm 0.15^{\circ}$. Parallelism between end facets F1 and F2 is within $\pm 5$ minutes.

5 Optical finish of facets F1 and F2 is within 20/10 scratch dig with $\lambda / 4 @ 633 \mathrm{~nm}$. No more than two $100 \mu \mathrm{~m}$ size chips per end facet.

6 Dual coating to less than $R<1 \%$ at $505-550 \mathrm{~nm}$ \& 1010-1100nm on both input/output facets.

Device Specification MSHG1080-0.5-xx


Please note these are calculated tuning curves only and actual values may vary.
For more information, please contact us at:

